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Surface chemistry and the corrosion behavior of magnetron sputtered niobium oxide films in sulfuric acid solution

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Abstract

In this work, magnetron sputtered Nb₂O₅ films were obtained at two different deposition times. The surface chemistry of the deposited layers was investigated by X-ray photoelectron spectroscopy (XPS). The corrosion behavior was assessed by electrochemical impedance spectroscopy, potentiodynamic polarization and potentiostatic polarization tests in 0.5 M H₂SO₄ + 2 ppm HF solution at room temperature. The Nb⁵⁺/Nb⁴⁺ ratio decreased with the deposition time, leading to a higher surface activity for the film obtained at 30 minutes. This result was confirmed by its lower impedance values and higher current densities when compared to the 15'-film. Surface chemistry played a major role on the corrosion behavior of the sputtered films and can be tailored by the deposition time.

Keywords: Nb₂O₅ films; magnetron sputtering; XPS; corrosion; sulfuric acid solution

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